

**ESI:**

**Nanostructured tin electrodeposited in ionic liquid for use as anode  
for Li-ion batteries**

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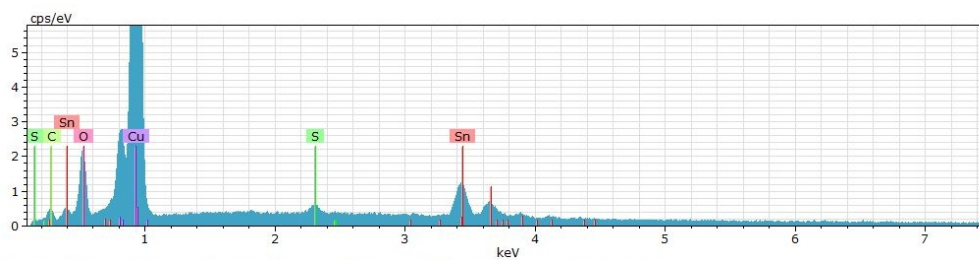
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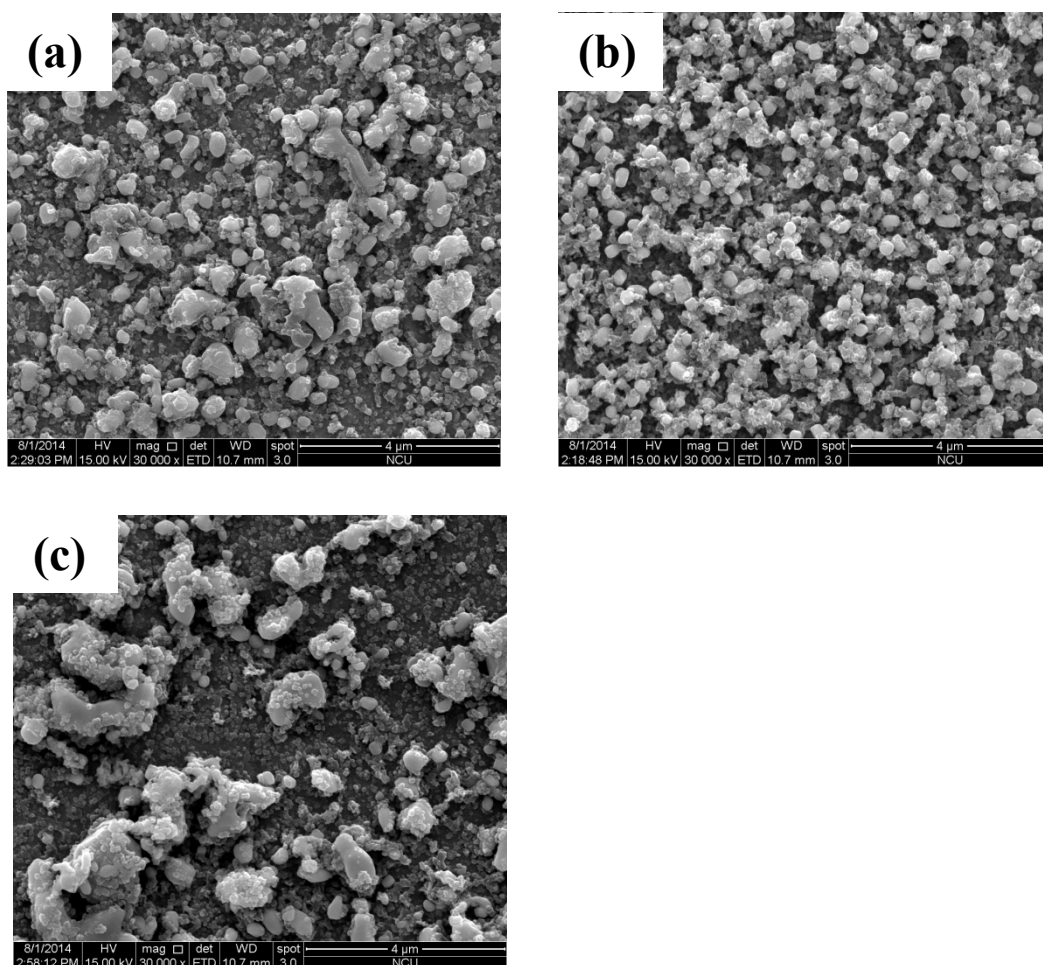
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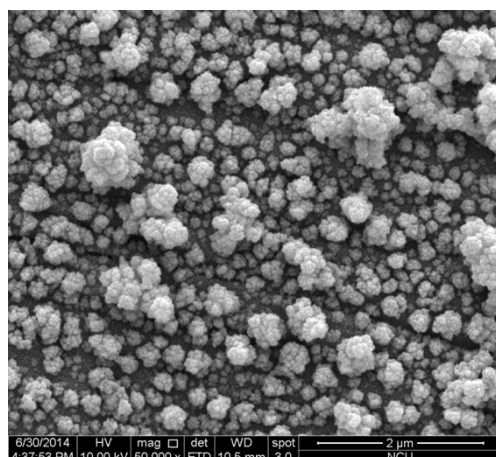


| El     | AN | Series   | unn. C<br>[wt.%] | norm. C<br>[wt.%] | Atom. C<br>[at.%] | Error (1 Sigma)<br>[wt.%] |
|--------|----|----------|------------------|-------------------|-------------------|---------------------------|
| Cu     | 29 | K-series | 75.09            | 83.09             | 66.14             | 2.45                      |
| O      | 8  | K-series | 4.92             | 5.44              | 17.21             | 0.79                      |
| C      | 6  | K-series | 2.65             | 2.94              | 12.37             | 0.63                      |
| Sn     | 50 | L-series | 7.20             | 7.97              | 3.40              | 0.26                      |
| S      | 16 | K-series | 0.51             | 0.56              | 0.88              | 0.05                      |
| Total: |    |          | 90.37            | 100.00            | 100.00            |                           |

**Figure S1** EDS data of Cu foil after being immersed in aqueous plating solution (consisted of 0.01 M  $\text{SnSO}_4$  and 0.25 M  $\text{H}_2\text{SO}_4$ ) for 8 h.



**Figure S2** SEM micrographs of Sn electrodes after 50 charge-discharge cycles. (a) is deposited at -1.2 V in IL plating solution, (b) is deposited at -2.4 V in IL plating solution, and (c) is deposited in aqueous solution.



**Figure S3** SEM micrograph of a Sn-Cu binary electrode electrodeposited in IL plating solution.